

# Study and optimization of the photovoltaic parameters ( $V_{oc}$ , $J_{cc}$ , $FF$ , $\eta$ ) by numerical simulation of two structures: n-Si/p-Si homojunction and n-ZnO/p-Si heterojunction with the SCAPS 1D software.

## ABSTRACT

In this article, numerical simulations of the electrical current-voltage characteristics of an n-Si / p-Si homojunction solar cell and an n-ZnO / p-Si heterojunction solar cell are performed. In order to find the optimal structure of the solar cells, numerical modelling using SCAPS-1D (Solar Cell Capacitance Simulator One Dimension) is performed. We study the effect of emitter and base thickness and doping on the cell output parameters which are open circuit voltage ( $V_{oc}$ ), short circuit current density ( $J_{cc}$ ), form factor ( $FF$ ) and conversion efficiency ( $\eta$ ). A comparison between the homojunction and heterojunction structure is also made in order to find which one of the two structures has the better conversion efficiency. We found that the efficiency of the n-ZnO / p-Si heterojunction is better than that of the n-Si / p-Si homojunction. Therefore, the presence of a transparent conductive oxide (TCO) such as an n-ZnO layer on p-type silicon can improve the conversion efficiency of the solar cell due to the anti-reflection effect of the TCO layer.

*Keywords: silicon, zinc oxide, solar cell, homojunction, heterojunction, Scaps-1*

## 1. Introduction

ZnO is a promising semiconductor material for various optoelectronic applications such as thin film solar cell , transparent conducting electrodes , light-emitting diodes (LEDs), due to its large direct bandgap (3.37 eV) and exciton binding energy (60 meV) at room temperature [1]. High transparency in visible spectrum range and wide bandgap make it a suitable candidate to be used as window layer in heterojunction solar cell. Due to its direct bandgap nature, ZnO absorption coefficient is very high which makes it a suitable material for the fabrication of thin film solar cell. Low processing temperature, nontoxicity, abundance, and excellent responsivity in UV region are some additional features of ZnO which can be effectively implemented to scale the growth of various optoelectronic devices [2].

The development of technology, for cost reduction still and increased performance with respect to the environment, remains challenging. Transparent conducting oxide (TCO) layer on the junction emitter is generally used to enhance the collection of carriers in commercial silicon solar cells. Indium Tin Oxide (ITO), though it has limited source on the earth, is often used as TCO material. Heterojunction solar cell with wide band gap semiconductor emitter layer, namely the zinc oxide (ZnO) layer on silicon absorber has attracted a great deal of interest among researchers in recent times due to its several advantages. Indeed, the processing cost for the deposition of ZnO thin film is low, ZnO is a TCO with good electrical and optical properties and finally it is a non-toxic material [3].

Intrinsically, ZnO is an *n*-type material due to the large number of unintentional defects incorporated and created during the process, with respect to the growth method. These defects are commonly believed to be Zn interstitial and oxygen vacancy. However, *n*-type conductivity of ZnO can be very beneficial to the current Si based thin film solar cell fabrication. Indeed, the emitter of a silicon solar cell is generally fabricated by a high temperature and long diffusion of phosphorus into the bulk silicon to form a pn junction. ZnO layer can be an alternative to the emitter formation by phosphorus diffusion due to its high *n*-type conductivity as well as antireflection coating. This will remove the high temperature diffusion step from the current Si solar cell fabrication process [4]. Using ZnO layer over Si provides a window for photon transfer, gives a higher built in potential to increase the open circuit voltage ( $V_{oc}$ ) and to passivate the surface and grain boundary defects and to reduce the dark current. In addition, in the *n*-ZnO/*p*-Si heterojunction solar cells, the solar light (the visible spectrum and near infrared) can be efficiently collected owing to the wide band gap of ZnO ( $E_g = 3.3$  eV).

There are many researches on *n*-ZnO/*p*-Si heterojunction solar cells. For example, without interface states density, Babar et al [5], by simulating a *n*-ZnO/*p*-Si solar cell, reported a conversion efficiency of about 19 %. Zeng et al fabricated B:ZnO/Si solar cell and reached a  $V_{oc}$  of 628 mV,  $J_{sc}$  of 41 mA .cm<sup>-2</sup> and efficiency of 17.78 %.

The performance of the heterojunction cell strongly depends on the doping concentration, the bulk defect density and the respective thicknesses of *n*-ZnO and *p*-Si layers. Indeed, modifying their properties affects both charge carrier transport at the junction (recombination, field effect) and photogeneration.

In order to optimize the performance of a solar cell, it is necessary to go through a step of simulation of these electrical components behavior and to examine the effect of the various manufacturing parameters on the output parameters of the cell. For this purpose, we use the SCAPS1-D (a solar cell capacitance simulator in one dimension) software for the simulation. We systematically study the effect of emitter and base thickness and the doping levels on the cell output parameters which are open circuit voltage ( $V_{oc}$ ), short circuit current density ( $J_{sc}$ ), form factor ( $FF$ ) and conversion efficiency ( $\eta$ ) of the *n*-Si / *p*-Si homojunction and the *n*-ZnO / *p*-Si heterojunction. Then we make a comparison between the homojunction and heterojunction structure with the aim to emphasize the role the TCO ZnO layer.

## 2. Methodology

Numerical Modeling has been increasingly used as a tool to understand the physical operation of the solar cells. Various measurements are done to understand the optical and electrical properties of the solar cell. However, it is difficult to analyze these measurements without the precise model. Therefore, numerical modeling is necessary to interpret the advanced measurement on complicated structures, to design and to optimize advanced cell structures. Following are the most important things to consider in simulation software: capability of solving the basic equations – Poisson equation and the continuity equation for electron and hole [4]. We used the SCAPS software to simulate the current-voltage characteristics of an n-Si/p-Si and n-ZnO/p-Si solar cell with the aim of identifying the optimal manufacturing and operating conditions of these cells.

SCAPS is simulation free software for one-dimensional solar cells developed by the Department of Electronic and Computer Systems of Ghent University, Belgium. SCAPS was originally developed for CuInSe<sub>2</sub> and CdTe cell structures. However, several versions have improved its capabilities to become applicable for crystalline solar cells (Si and GaAs) and amorphous cells (a-Si and micro amorphous Si) [6]. With SCAPS, it is possible to simulate structures consisting of a defined number of layers (up to 7 interlayers as well as front and back contacts) with different doping profiles, and with given energy distributions of donor or acceptor levels, in the bulk and at the interfaces for an arbitrary light spectrum [7].

Simulation with SCAPS requires knowledge of the values of a number of physical parameters of the materials used. These parameters are defined in the SCAPS software interface. In the case of the n-Si/p-Si homojunction, the values are presented in Table 1.

**Table 1:: Physical parameters of silicon introduced in SCAPS[4].**

Parameters	Definition	Values
$\epsilon_r$	Relative Permittivity	11.9
$E_g(\text{eV})$	Energy gap	1.12
$\chi(\text{eV})$	Electronic affinity	4.05
$N_c(\text{cm}^{-3})$	Effective density of states in the conduction band	$2.8 \cdot 10^{19}$
$N_v(\text{cm}^{-3})$	Effective density of states in the valence band	$1.04 \cdot 10^{18}$
$\mu_n(\text{cm}^2/\text{Vs})$	Electron mobility	1500
$\mu_p(\text{cm}^2/\text{Vs})$	Hole mobility	480
$V_{\text{the}}(\text{cm/s})$	Thermal velocity of electrons	$10^7$
$V_{\text{thh}}(\text{cm/s})$	Thermal velocity of Hole	$10^7$
T(K)	Temperature	300

Unlike Si, ZnO cannot be used alone in a solar cell because its p-type doping is difficult to achieve and only leads to low hole concentrations. This is due to the combined effects of two properties of ZnO: it is naturally n-type and a large band gap semiconductor. This difficulty in achieving p-type conductivity is general to all large gap semiconductors. As a result, ZnO is often combined with other p-type

materials such as silicon to form heterojunction. The physical parameters of the heterojunction cell defined in the SCAPS software are presented in Table 2.

**Table 2: n-ZnO/p-Si physical parameters introduced in SCAPS [4].**

Parameters	Definition	n-ZnO	p-si
$\epsilon_r$	Relative Permittivity	9	11.9
$E_g$ (eV)	Energy gap	3,3	1.12
$\chi$ (eV)	Electronic affinity	4,35	4.05
$N_c$ (cm <sup>-3</sup> )	Effective density of states in the conduction band	4,410 <sup>18</sup>	2.8 10 <sup>19</sup>
$N_v$ (cm <sup>-3</sup> )	Effective density of states in the valence band	7,1 10 <sup>19</sup>	1.04 10 <sup>18</sup>
$\mu_n$ (cm <sup>2</sup> /Vs)	Electron mobility	100	1500
$\mu_p$ (cm <sup>2</sup> /Vs)	Hole mobility	25	480
$V_{the}$ (cm/s)	Thermal velocity of electrons	10 <sup>7</sup>	10 <sup>7</sup>
$V_{thh}$ (cm/s)	Thermal velocity of Hole	10 <sup>7</sup>	10 <sup>7</sup>
T(K)	Temperature	300	300

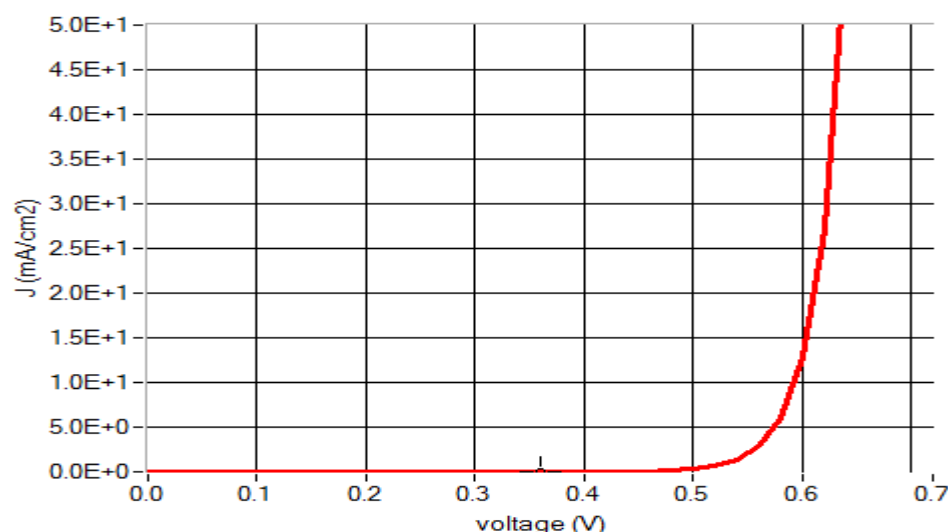
### 3. RESULTS AND DISCUSSION

In this section, the simulation results of n-Si/p-Si homojunction and n-ZnO/p-Si heterojunction solar cells are presented. The current-voltage characteristics in the dark and under illumination, at the 1.5 air mass spectrum (AM) were simulated.

#### 3.1. n-Si/p-Si homojunction solar cell

##### 3.1.1. Current-voltage curve in the dark

A typical example of the current-voltage characteristic in the dark with SCAPS simulation is represented in **figure 1**. This curve is obtained with the values given in table 1 with an emitter thickness of 0.1  $\mu\text{m}$ , an emitter doping with donor densities  $N_d = 3 \cdot 10^{18} \text{ cm}^{-3}$  and a collector doping with acceptor densities  $N_a = 10^{16} \text{ cm}^{-3}$  for a collector thickness of 200  $\mu\text{m}$ . We can notice on this curve that the current density remains invariable for low voltages up to 0.5V, then varies in an exponential way for important values of the voltage (higher than 0.5V). This means that the cell will produce current only for voltages higher than 0.5V and in a very efficient way.



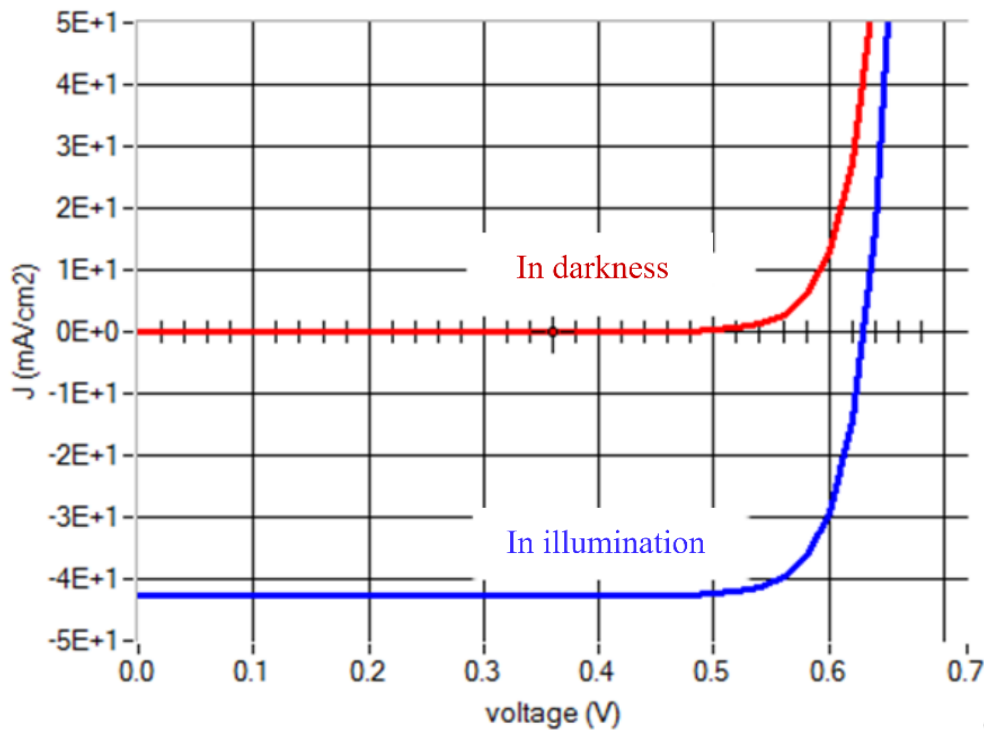
**Figure 1: Current-voltage curve in the dark.**

### 3.1.2. Current-voltage curve in darkness and illumination

For the simulation under illumination, the light spectrum we have used is AM1.5G and SCAPS allows automatic loading of the chosen spectrum.

**Figure 2** gives the current-voltage characteristics under darkness and under illumination.

The curve under illumination has an offset from the dark curve and this offset corresponds to the photo-current generated ( $J_{ph}$ ).



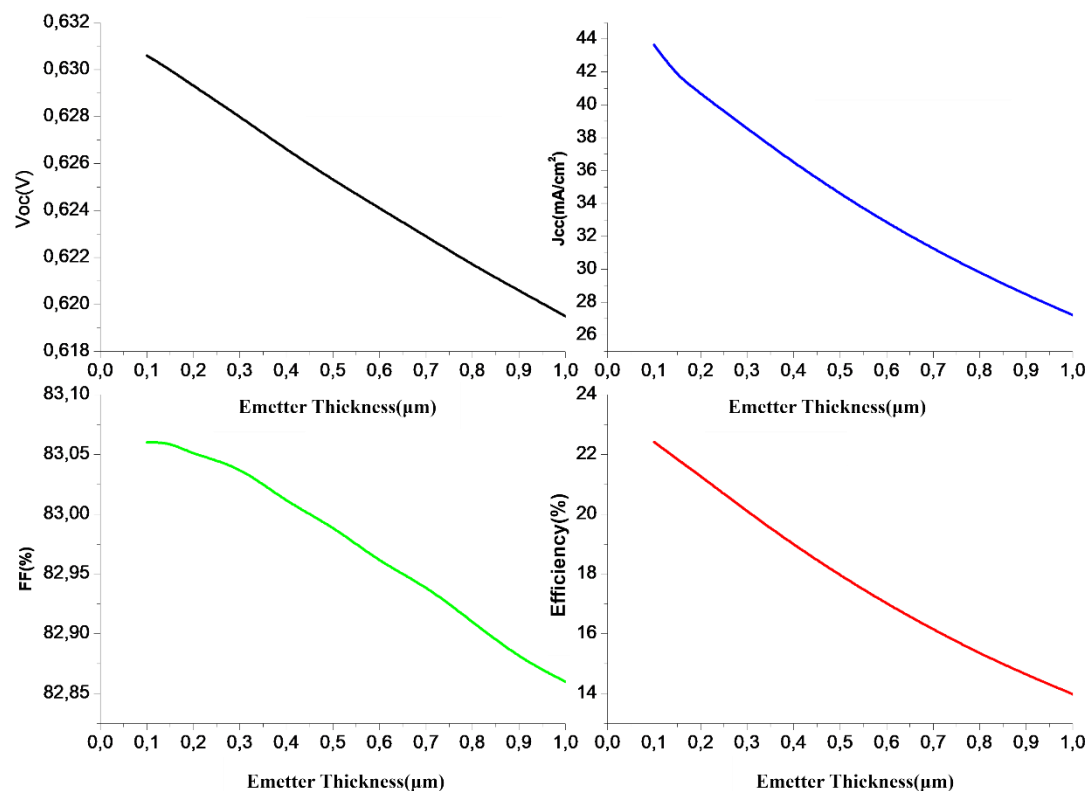
**Figure 2: Current-voltage characteristic in darkness and under illumination**

### 3.1.3. Effect of emitter thickness

We have varied the thickness of the emitter from 0.1 to  $1\mu\text{m}$  while keeping constant the other values of table1. The choice of this range of thickness is guided by what it is possible to do experimentally. The values of the photovoltaic parameters ( $V_{oc}$ ,  $J_{cc}$ , FF,  $\eta$ ) obtained as a function of the emitter thickness are presented in **Figure 3**. With the increase of the emitter thickness, we notice a decrease of the output parameters. Thus  $V_{oc}$  decreases from 0.63 to 0.62 V,  $J_{cc}$  from 44.64 to 27.21  $\text{mA}/\text{cm}^2$ , FF from 83.06 to 82.86% and finally the conversion efficiency of the cell decreases, from 22.41% to 13.97%. From these values, we can see that  $J_{cc}$  and efficiency  $\eta$  are the two most sensitive parameters to an increase in emitter thickness.

For small thicknesses, the electron-hole pair generation phenomenon occurs near the interfaces so the surface recombinations increase, which reduces the number of electron-hole pairs. On the other hand, the emitter layer must be as thin as possible to allow the full intensity of the light to pass through. When the thickness of the layer increases, the life span of the minority carriers does not allow them to cross the junction, so they recombine. They no longer have the possibility of crossing the

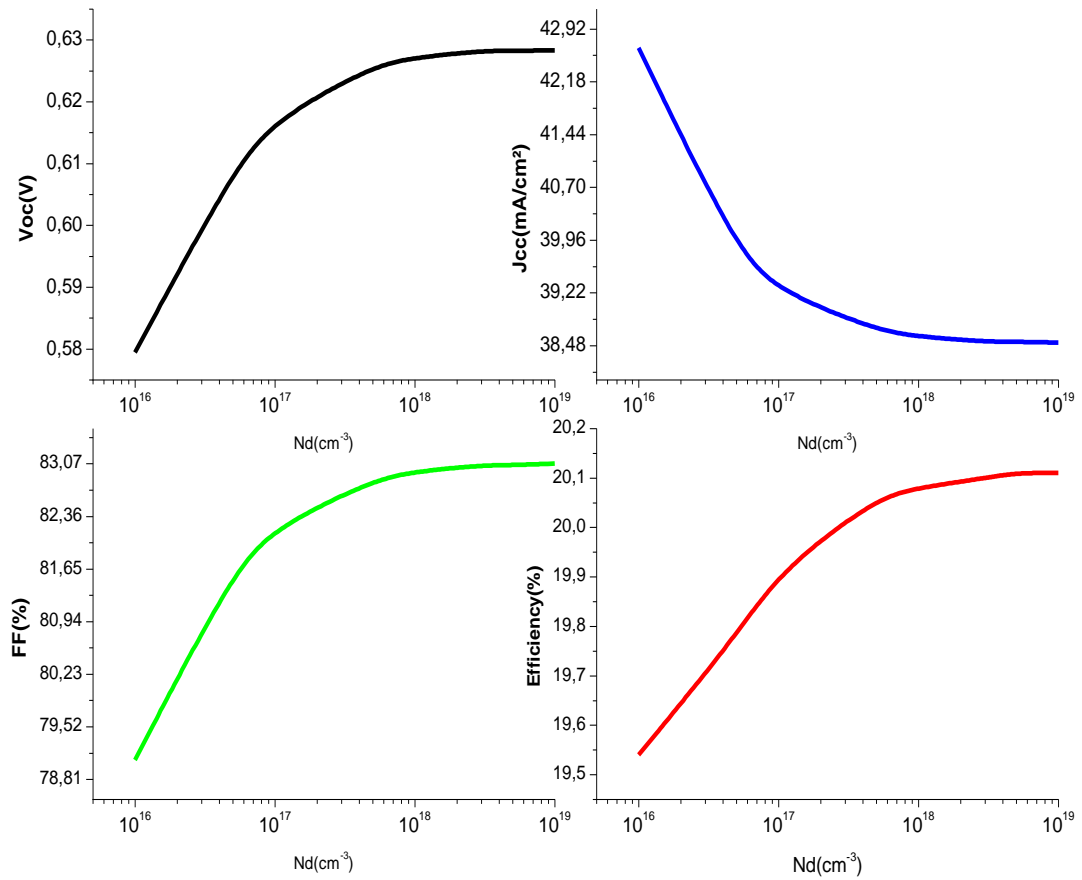
junction to be collected. This explains the decrease in photovoltaic parameters. A thin emitting layer therefore increases the transmitted flux. It is concluded that the thinner the layer, the higher the efficiency [8]. However, if the layer is too thin, surface recombination phenomenon increases.



**Figure 3: Variation of photovoltaic parameters with the effect of emitter thickness.**

### 3.1.4 Effect of emitter doping

To study the effect of the cell's emitter doping, we varied only the  $N_d$  concentration from  $10^{16}$  to  $10^{19}$   $\text{cm}^{-3}$ , while keeping the other values given in Table 1 constant. We chose an emitter thickness of 0.3  $\mu\text{m}$ . **Figure 4** shows the photovoltaic parameters of the cell variations as a function of  $N_d$  doping. In this case, a decrease in  $J_{cc}$  from 44.65 to 38.52  $\text{mA}/\text{cm}^2$  is observed with a change in emitter doping from  $10^{16}$  to  $10^{19}$   $\text{cm}^{-3}$ .  $V_{oc}$  increases from 0.58 to 0.63,  $FF$  also shows an increase and finally an improvement in conversion efficiency is noticed from 19.54 to 20.11% for the same doping range. The increase in doping allows an improvement in the conversion efficiency of the structure. Indeed, with the increase in doping, the lifetime of the minority carriers and the mobility increase. We found that the efficiency increases despite the large presence of impurities. These impurities are added to increase the electrical conductivity or to control the carrier lifetime. On the other hand, as the doping of the emitter layer increases, the potential barrier in the junction increases and the space charge area decreases. The increase in the barrier decreases the diffusion currents and increases the photogenerated current. The decrease in the space charge zone results in a decrease in the current  $J_{cc}$  because this current comes from the photogenerated carriers in this zone. The increase in efficiency is related to  $V_{oc}$  and  $FF$  [8].

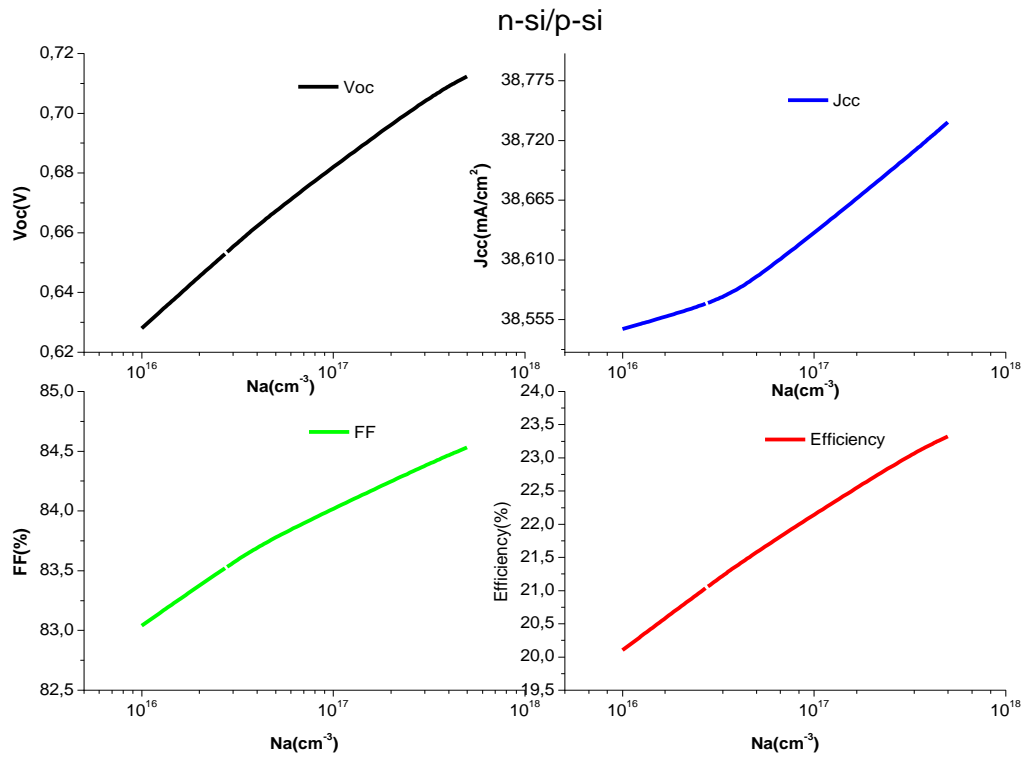


**Figure 4: Photovoltaic parameters as a function of emitter Nd doping**

### 3.1.5 Effect of collector doping

We also varied the  $N_a$  doping density of the base from  $10^{16}$  to  $10^{18} \text{ cm}^{-3}$ . The variations of the photovoltaic parameters ( $J_{cc}$ ,  $V_{oc}$ ,  $FF$ ,  $\eta$ ) as a function of  $N_a$  doping are shown in **Figure 5**.

With the increase of the  $N_a$  doping density of the base which constitutes the collector, we notice a small variation of  $J_{cc}$ . Indeed,  $J_{cc}$  varies from 38.54 to 38.78  $\text{mA/cm}^2$ . This small variation is attributed to the narrowing of the width of the depletion zone that occurs in the collector region with the increase in doping density and an increase in  $V_{oc}$ ,  $FF$  and finally the efficiency of the cell increases from 20.1 to 23.64%. Indeed, the increase in doping enhances the potential difference between the n and p regions, therefore  $V_{oc}$  and  $FF$  and the efficiency increase.



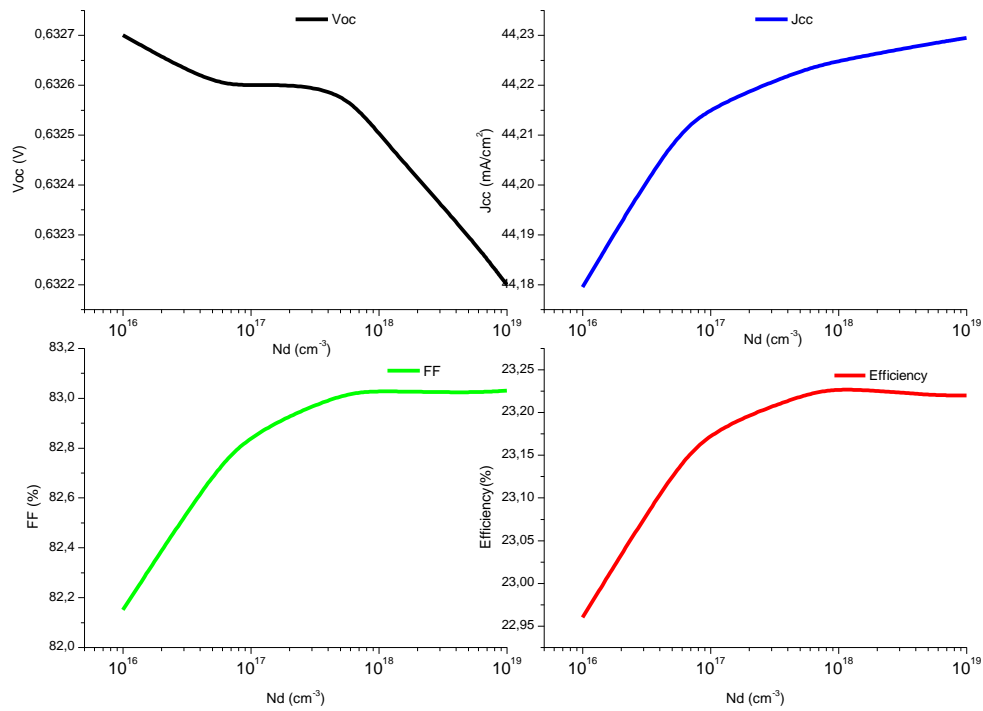
**Figure 5: Photovoltaic parameter characteristics as a function of Na doping**

### 3.2. n-ZnO/p-Si heterojunction solar cell

#### 3.2.1 Effect of doping the n-ZnO

In this section, we study the effect of  $N_d$  doping density of the n-ZnO emitter of the heterojunction cell. For this purpose, we have varied the  $N_d$  doping concentration from  $10^{16}$  to  $10^{19} \text{ cm}^{-3}$ , while using the values in Table 2. **Figure 6** represents the variations of the photovoltaic parameters ( $J_{cc}$ ,  $V_{oc}$ , FF and efficiency) of the heterojunction cell as a function of the  $N_d$  doping density of the emitter. A very small variation in the voltage  $V_{oc}$  and current  $J_{cc}$  is observed with the variation of the emitter doping density. The FF shows an increase and an improvement in conversion efficiency is noticed. This can be explained by the fact that with its high band gap, the ZnO layer allows visible radiation to pass through. This layer is also a transparent conductive oxide and acts as an anti-reflective layer to trap the refracted rays from the silicon. Thus, the absorption at the silicon is improved and the charged carrier creation is optimized.



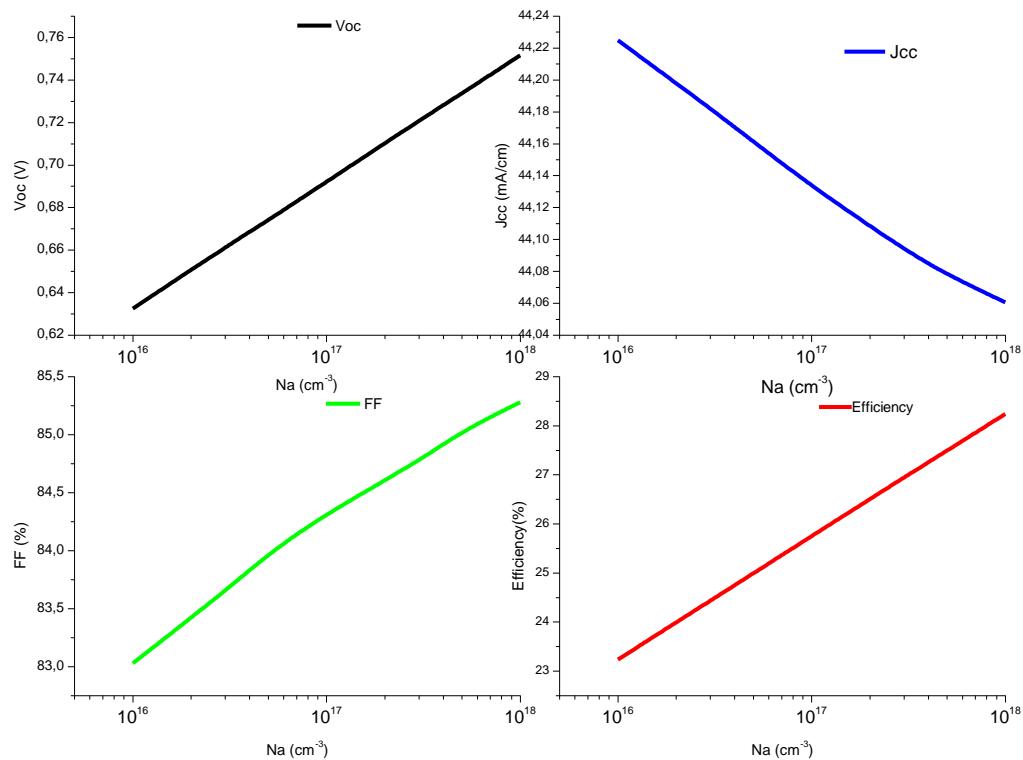


**Figure 6: Variations in electrical parameters as a function of Nd doping of the n-ZnO**

### 3.2.2 Effect of p-Si base doping on the heterojunction

To study the effect of  $N_a$  doping of the base (p-Si layer) of the heterojunction, we have used the values given in Table 2 with a variation of  $N_a$  doping density from  $10^{16}$  to  $10^{18} \text{ cm}^{-3}$ . **Figure 7** shows the variation of the photovoltaic parameters of the heterojunction cell as a function of the  $N_a$  doping of the p-Si collector.

With the doping of the p-Si region which forms the base of the heterojunction, we observe a small decrease in  $J_{cc}$  and an increase in  $V_{oc}$ ,  $FF$  and finally in the efficiency of the n-ZnO/p-Si solar cell from 23.23 to 28.24%, respectively for  $N_a$  doping density of  $10^{16}$  to  $10^{18} \text{ cm}^{-3}$ . The increase in collector doping density leads to a narrowing of the width of the depletion zone that occurs in the collector region. Subsequently the collection of photogenerated carriers will be affected, because it is the internal field of the depletion zone that ensures the dissociation and collection of photogenerated electrons and holes. But as the increase in doping density on the other side enhances the potential difference between the n and p regions, then  $V_{oc}$  and  $FF$  increase and so does the efficiency.



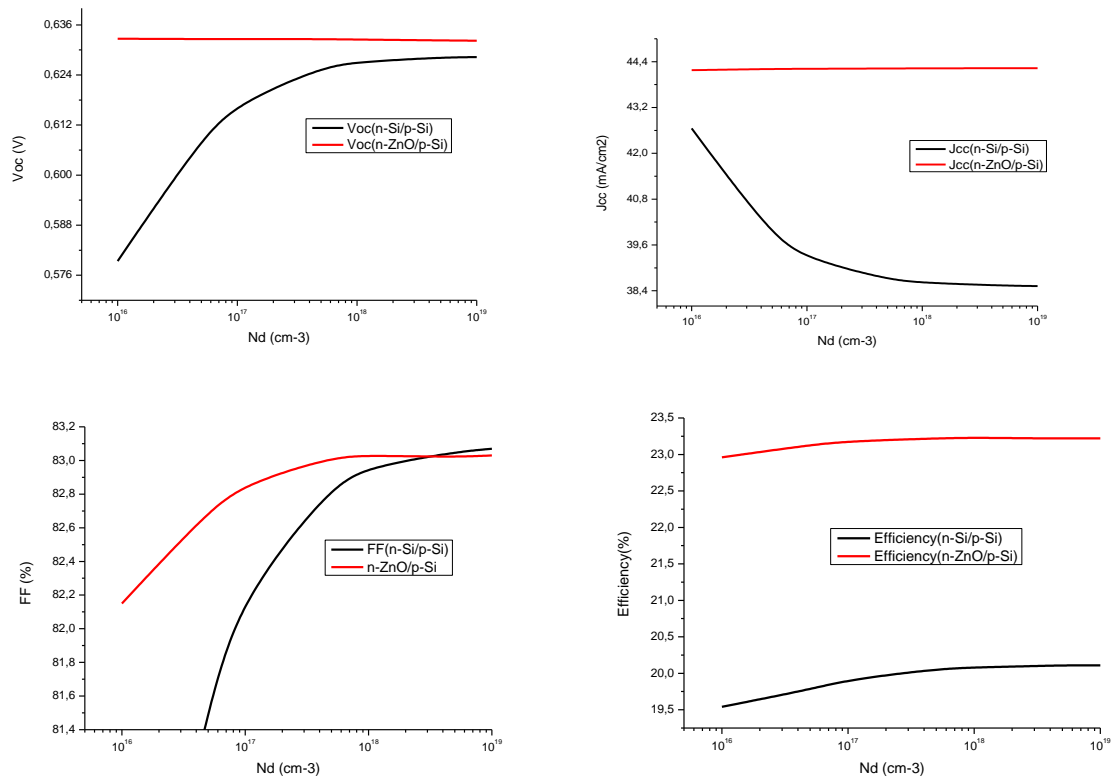
**Figure 7: Variations of photovoltaic parameters as a function of Na doping of the p-Si collector of the n-ZnO/p-Si heterojunction.**

### 3.3. Comparison of the two structures

With the n-ZnO layer as emitter in the n-ZnO/p-Si heterojunction, there is a slight increase in  $V_{oc}$ , a significant increase in current  $J_{cc}$  and almost the same FF and finally an increase in efficiency compared to the electrical parameters ( $V_{oc}$ ,  $J_{cc}$ , FF, efficiency) of the silicon-based np homojunction cell.

#### 3.3.1 Comparison of the effect of emitter doping on the two structures

In this section, we compare the variation of the photovoltaic parameters of our two structures (homojunction and heterojunction) upon the effect of the doping of their respective emitters. **Figure 8** shows that the emitter doping has a much more important effect on  $V_{oc}$  and  $J_{cc}$  of the homojunction than those of the heterojunction and as for the FF and efficiency, we observe for both structures practically the same types of variation.

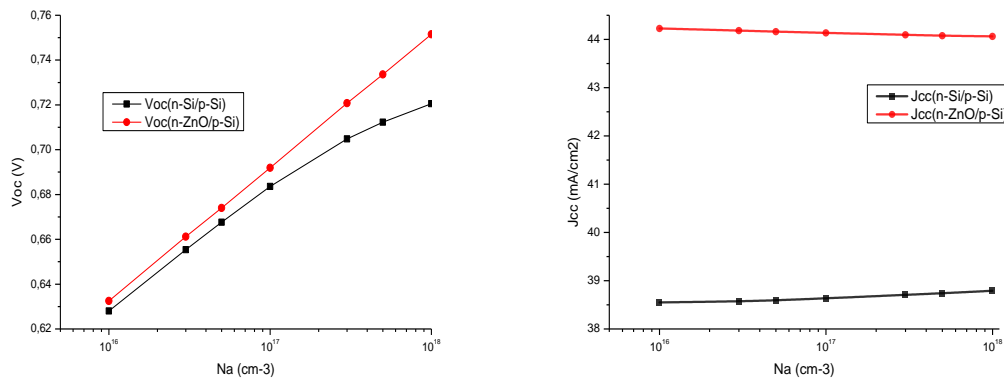


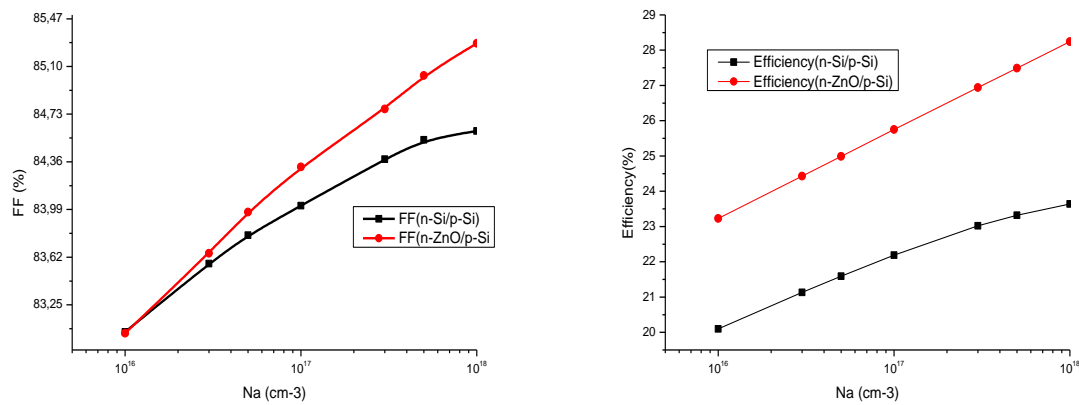
**Figure 8: Variation of the photovoltaic output parameters of two structures with Nd doping**

### 3.3.2 Comparison of the effect of doping the base of the two structures

**Figure 9** shows the effect of  $N_a$  doping on different electrical output parameters of our two structures. It can be seen that with the base doping of the two structures, the photovoltaic parameters  $V_{oc}$ ,  $J_{cc}$ , FF and the efficiency show the same types of variations.

With the variations of  $N_d$  and then  $N_a$  for both structures, the **figure 8** and **figure 9** show us that the electrical parameters of the heterojunction solar cell remain better than those of the silicon based homojunction cell. We can conclude that the performance of the heterojunction is better than that of the homojunction for given doping density.





**Figure 9: Electrical output characteristics of two structures with Na**

To illustrate this fact, we give in table 3 the photovoltaic parameters of the two structures for an emitter thickness of 0.3  $\mu\text{m}$ , a collector thickness of 200  $\mu\text{m}$ , a doping density of the emitter  $N_d = 10^{18} \text{ cm}^{-3}$  and a doping density of the base  $N_a = 10^{16} \text{ cm}^{-3}$ . We observe an efficiency of 23.23% for the heterojunction and 20.08% for the homojunction.

**Table 3: Photovoltaic parameters of the two structures (homojunction and heterojunction)**

$N_d = 10^{18} \text{ cm}^{-3}$ $N_a = 10^{16} \text{ cm}^{-3}$ $d_n(\text{emitter thickness}) = 0.3 \mu\text{m}$ $d_p(\text{base thickness}) = 200 \mu\text{m}$				
Parameters	Voc(V)	Jcc (mA/cm²)	FF(%)	Efficiency (%)
n-Si/p-Si	0.6271	38.61	82.96	20.08
n-ZnO/p-Si	0.6325	44.23	83.03	23.23

#### 4. CONCLUSION

In this study, we have performed numerical simulations of the electrical current-voltage characteristics of an n-Si / p-Si homojunction solar cell and an n-ZnO / p-Si heterojunction solar cell. We have examined the effect of the solar cell emitter and base doping and thickness on the output parameters such as  $V_{oc}$ ,  $J_{cc}$ , FF, efficiency. Thus, the n-Si/p-Si cell homojunction solar presents an efficiency of 20.08%, for an emitter of 0.3  $\mu\text{m}$  thickness and doping of  $10^{18} \text{ cm}^{-3}$  and a base of 200  $\mu\text{m}$  thickness with a doping of  $10^{16} \text{ cm}^{-3}$ . Whereas, for the heterojunction structure, we obtain an efficiency of 23.23% with the same parameters that is a 0.3  $\mu\text{m}$  thick emitter with a doping of  $10^{18} \text{ cm}^{-3}$  and a base of 200  $\mu\text{m}$  with a doping of  $10^{16} \text{ cm}^{-3}$ . Therefore, heterojunction solar cell shows a better performance compared to the n-Si/p-Si cell. This is due to the transparent conductive oxide character of ZnO which acts as an anti-reflection layer thus trapping the refracted rays from the silicon. This leads to an improvement of the absorption at the silicon increasing the electron-hole pair creation.

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